

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	15	(mask same interfeat\$4) and layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/16 09:50
L2	4607	(mask same inspect\$4) and layer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/16 09:50
L3	2	(mask same inspect\$4) and layer and interfeat\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/16 09:54
L4	321	(mask same inspect\$4) and layer and opc	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/16 09:56
L5	97	(mask same inspect\$4) and layer and opc and relationship	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/16 09:56
L6	92	(mask same inspect\$4) and layer and opc and relationship and feature	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/16 09:57
L7	75	(mask same inspect\$4) and layer and opc and relationship and feature and lithography	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/16 09:57
L8	70	(mask same inspect\$4) and layer and opc and relationship and feature and lithography and wafer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/16 10:08

L9	49	(mask same inspect\$4) and layer and opc and relationship and feature and lithography and wafer and ("716"/\$.ccls. or "430"/\$.ccls. or "702"/\$.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/16 10:15
L10	31	(mask same inspect\$4) and layer and opc and relationship and feature and lithography and wafer and ("716"/\$.ccls. or "430"/\$.ccls. or "702"/\$.ccls.) and writ\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/16 10:32
L11	31	(mask same inspect\$4) and layer and opc and relationship and feature and lithography and wafer and ("716"/\$.ccls. or "430"/\$.ccls. or "702"/\$.ccls.) and writ\$4 and data	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/16 10:35
L12	14	(mask same inspect\$4) and layer and opc and relationship and feature and lithography and wafer and ("716"/\$.ccls. or "430"/\$.ccls. or "702"/\$.ccls.) and writ\$4 and data and criteria	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/16 10:35

	Document ID	Issue Date	Title
1	US 20050076316 A1	20050407	Design-manufacturing interface via a unified model
2	US 20050060680 A1	20050317	Rule based system and method for automatically generating photomask orders in a specified order format
3	US 20050055659 A1	20050310	Rule based system and method for automatically generating photomask orders by conditioning information from a customer's computer system
4	US 20040133369 A1	20040708	Method and system for context-specific mask inspection
5	US 20040107412 A1	20040603	Method and system for context-specific mask writing
6	US 20040025137 A1	20040205	Rule based system and method for automatically generating photomask orders in a specified order format
7	US 20030126581 A1	20030703	User interface for a network-based mask defect printability analysis system
8	US 20030088847 A1	20030508	Method of incorporating lens aberration information into various process flows
9	US 20020026626 A1	20020228	Optical proximity correction
10	US 6880135 B2	20050412	Method of incorporating lens aberration information into various process flows
11	US 6842881 B2	20050111	Rule based system and method for automatically generating photomask orders in a specified order format
12	US 6634018 B2	20031014	Optical proximity correction
13	US 6578188 B1	20030610	Method and apparatus for a network-based mask defect printability analysis system
14	US 5657235 A	19970812	Continuous scale optical proximity correction by mask maker dose modulation